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=> fil reg
FILE 'REGISTRY' ENTERED AT 10:19:42 ON 01 DEC 2008
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STRUCTURE FILE UPDATES:   28 NOV 2008  HIGHEST RN 1076692-21-1
DICTIONARY FILE UPDATES:  28 NOV 2008  HIGHEST RN 1076692-21-1

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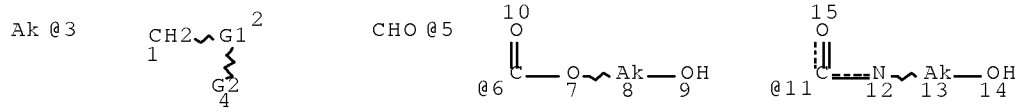
on property searching in REGISTRY, refer to:

http://www.cas.org/support/stngen/stndoc/properties.html

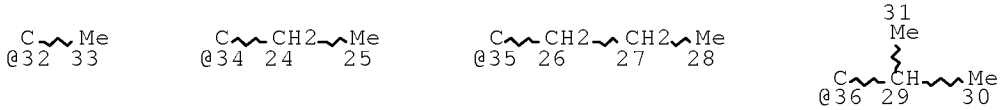
=> d que stat l25
L1              SCR 2043
L2              STR
```

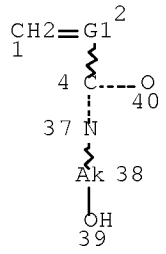



```
VAR G1=CH/3
VAR G2=5/6/11
NODE ATTRIBUTES:
CONNECT IS E2  RC AT   8
CONNECT IS E2  RC AT  13
DEFAULT MLEVEL IS ATOM
GGCAT   IS SAT  AT   3
GGCAT   IS SAT  AT   8
GGCAT   IS SAT  AT  13
DEFAULT ECLEVEL IS LIMITED
ECOUNT  IS M2-X4 C  AT   3

GRAPH ATTRIBUTES:
RING(S) ARE ISOLATED OR EMBEDDED
NUMBER OF NODES IS  15

STEREO ATTRIBUTES: NONE
L3              SCR 2016 OR 2026 OR 2021
L4        63135 SEA FILE=REGISTRY SSS FUL L2 AND L1 NOT L3
L19             STR
```

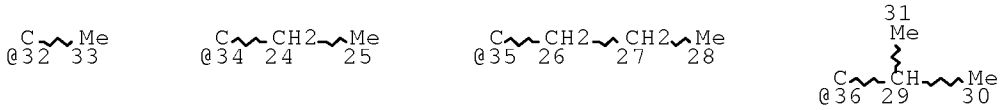


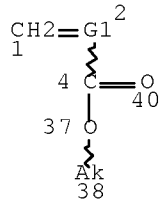


VAR G1=CH/32/34/35/36
NODE ATTRIBUTES:
CONNECT IS E2 RC AT 38
DEFAULT MLEVEL IS ATOM
GGCAT IS SAT AT 38
DEFAULT ECLEVEL IS LIMITED
ECOUNT IS X3 C AT 38

GRAPH ATTRIBUTES:
RING(S) ARE ISOLATED OR EMBEDDED
NUMBER OF NODES IS 20

STEREO ATTRIBUTES: NONE
L20 STR





VAR G1=CH/32/34/35/36
NODE ATTRIBUTES:
CONNECT IS E1 RC AT 38
DEFAULT MLEVEL IS ATOM
GGCAT IS SAT AT 38
DEFAULT ECLEVEL IS LIMITED
ECOUNT IS X3 C AT 38

GRAPH ATTRIBUTES:
RING(S) ARE ISOLATED OR EMBEDDED
NUMBER OF NODES IS 19

STEREO ATTRIBUTES: NONE
L24 1732 SEA FILE=REGISTRY SUB=L4 SSS FUL L19 AND L20

```
L25          16 SEA FILE=REGISTRY ABB=ON  PLU=ON  L24 NOT NC>=3


=> d his nofile

     (FILE 'HOME' ENTERED AT 11:03:54 ON 26 NOV 2008)

     FILE 'HCAPLUS' ENTERED AT 11:04:26 ON 26 NOV 2008
L1            1 SEA ABB=ON  PLU=ON  US20070081048/PN
                SEL RN

     FILE 'REGISTRY' ENTERED AT 11:05:04 ON 26 NOV 2008
L2            5 SEA ABB=ON  PLU=ON  (25086-15-1/BI OR 26355-01-1/BI OR
                3089-11-0/BI OR 643090-86-2/BI OR 911204-98-3/BI)
                D SCA

     FILE 'LREGISTRY' ENTERED AT 11:40:57 ON 26 NOV 2008
L3              STR

     FILE 'REGISTRY' ENTERED AT 11:51:30 ON 26 NOV 2008
L4              SCR 2043
L5           50 SEA SSS SAM L3 AND L4
L6              SCR 2077
L7           15 SEA SSS SAM L3 AND L4 NOT L6
L8              STR L3
L9           50 SEA SSS SAM L8 AND L4
L10          29 SEA SSS SAM L8 AND L4 NOT L6
L11             SCR 2016 OR 2026 OR 2021
L12          50 SEA SSS SAM L8 AND L4 NOT L11
L13       63135 SEA SSS FUL L8 AND L4 NOT L11
L14           1 SEA ABB=ON  PLU=ON  L2 AND L13
                SAV TEMP L13 EOF255/A

     FILE 'LREGISTRY' ENTERED AT 12:17:37 ON 26 NOV 2008
L15             STR L8

     FILE 'REGISTRY' ENTERED AT 12:25:06 ON 26 NOV 2008
L16          50 SEA SUB=L13 SSS SAM L15

     FILE 'LREGISTRY' ENTERED AT 12:27:12 ON 26 NOV 2008
L17             STR L15

     FILE 'REGISTRY' ENTERED AT 12:30:08 ON 26 NOV 2008
L18          50 SEA SUB=L13 SSS SAM L17

     FILE 'LREGISTRY' ENTERED AT 12:34:31 ON 26 NOV 2008
L19             STR L17

     FILE 'REGISTRY' ENTERED AT 12:37:19 ON 26 NOV 2008
L20          50 SEA SUB=L13 SSS SAM L19
L21       57247 SEA SUB=L13 SSS FUL L19
L22           1 SEA ABB=ON  PLU=ON  L2 AND L21
                SAV L21 EOF255S1/A
L23        4423 SEA ABB=ON  PLU=ON  L21 NOT NC>=3
L24       57247 SEA ABB=ON  PLU=ON  L21 NOT RC>=2
L25         181 SEA ABB=ON  PLU=ON  L21 NOT NC>=2

     FILE 'LREGISTRY' ENTERED AT 12:49:42 ON 26 NOV 2008
L26             STR L19
```

```
     FILE 'REGISTRY' ENTERED AT 12:56:48 ON 26 NOV 2008
L27           50 SEA SUB=L13 SSS SAM L26 AND L19
L28        34226 SEA SUB=L13 SSS FUL L26 AND L19
                 SAV L28 EOF255S2/A
L29          338 SEA ABB=ON  PLU=ON  L28 NOT NC>=3
L30            1 SEA ABB=ON  PLU=ON  L29 AND L2
                 D RN
L31          519 SEA ABB=ON  PLU=ON  L25 OR L29

     FILE 'HCAPLUS' ENTERED AT 13:03:11 ON 26 NOV 2008
L32              QUE ABB=ON  PLU=ON  (PHOTO OR LIGHT)(A)SENS? OR PHOTOSENS
                 ? OR LIGHTSENS? OR PHOTOACTIVE? OR PHOTOREACTIV? OR
                 LITHO? OR PHOTOLITHO?
L33          313 SEA ABB=ON  PLU=ON  L31(L)L32
L34         1037 SEA ABB=ON  PLU=ON  L30
L35           60 SEA ABB=ON  PLU=ON  L33 AND L34
L36           58 SEA ABB=ON  PLU=ON  L35 AND (PY<=2005 OR PRY<=2005 OR
                 AY<=2005)
L37              QUE ABB=ON  PLU=ON  COMPOSITION
L38           18 SEA ABB=ON  PLU=ON  L36 AND L37
L39          141 SEA ABB=ON  PLU=ON  L33 AND L37
L40              QUE ABB=ON  PLU=ON  COMPOSITION/TI
L41           85 SEA ABB=ON  PLU=ON  L39 AND L40
L42          282 SEA ABB=ON  PLU=ON  L33 AND (PY<=2005 OR PRY<=2005 OR
                 AY<=2005)
L43           75 SEA ABB=ON  PLU=ON  L41 AND L42
L44           63 SEA ABB=ON  PLU=ON  L43 NOT L38
L45         1160 SEA ABB=ON  PLU=ON  L31(L)L37
L46           58 SEA ABB=ON  PLU=ON  L44 AND L45
L47        20415 SEA ABB=ON  PLU=ON  L32(3A)L37
L48           58 SEA ABB=ON  PLU=ON  L46 AND L47


=> fil hcap
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FILE COVERS 1907 - 1 Dec 2008  VOL 149 ISS 23
FILE LAST UPDATED: 30 Nov 2008  (20081130/ED)

HCAplus now includes complete International Patent Classification (IPC)
reclassification data for the third quarter of 2008.

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 This file contains CAS Registry Numbers for easy and accurate
 substance identification.
```

=> d ibib abs hitstr hitind l29 1-11

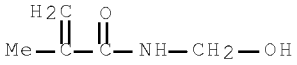
L29 ANSWER 1 OF 11 HCAPLUS COPYRIGHT 2008 ACS on STN
ACCESSION NUMBER: 2006:543953 HCAPLUS Full-text
DOCUMENT NUMBER: 145:37339
TITLE: Photosensitive resin composition, ink jet recording head using such composition and method for manufacturing such recording head
INVENTOR(S): Ishikura, Hiroe; Shiba, Shoji; Okano, Akihiko
PATENT ASSIGNEE(S): Canon Kabushiki Kaisha, Japan
SOURCE: U.S. Pat. Appl. Publ., 14 pp.
CODEN: USXXCO
DOCUMENT TYPE: Patent
LANGUAGE: English
FAMILY ACC. NUM. COUNT: 1
PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
US 20060117564	A1	20060608	US 2005-291956	200512 02
JP 2006162769	A	20060622	JP 2004-351347	200412 03
PRIORITY APPLN. INFO.:			JP 2004-351347 A	200412 03

AB The present invention provides a method for manufacturing a high quality ink jet head, and an ink jet head manufactured by such a method, in which, in a case where a coating resin layer constituting ink flow path walls is formed, even when a solvent having a strong dissolving force is used, it is not feared that a configuration of an ink flow path pattern is distorted. In the method, a photosensitive resin composition layer in which an inter-mol. bridging reaction proceeds by irradiation of an ionization radiant ray having a first wavelength band and a mol. decaying reaction of main chain decomposing type of the resin proceeds by irradiation of an ionization radiant ray having a second wavelength band different from the first wavelength band is formed on a substrate on which energy generating elements were provided. Thereafter, an ink flow path pattern is formed by the irradiation of the ionization radiant ray having the first wavelength band and a developing process. Then, a coating resin layer constituting ink flow path walls is formed on the ink flow path pattern. After ink discharge ports are formed, the photosensitive resin composition layer forming the ink flow path pattern is dissolved and removed by irradiating the ionization radiant ray having the second wavelength band.
IT 31292-66-7, Hydroxymethyl methacrylamide-methyl methacrylate copolymer
RL: DEV (Device component use); TEM (Technical or engineered material use); USES (Uses)
(photosensitive resin composition, ink jet recording head using such composition and method for manufacturing such recording head)
RN 31292-66-7 HCAPLUS
CN 2-Propenoic acid, 2-methyl-, methyl ester, polymer with N-(hydroxymethyl)-2-methyl-2-propenamide (9CI) (CA INDEX NAME)

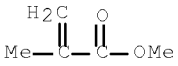
CM 1

CRN 923-02-4
CMF C5 H9 N O2



CM 2

CRN 80-62-6
CMF C5 H8 O2



INCL 029890100; 347001000; 430270100
CC 74-6 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)
Section cross-reference(s): 38
IT 26141-88-8, Glycidyl methacrylate-methyl methacrylate copolymer 31260-64-7 31292-66-7, Hydroxymethyl methacrylamide-methyl methacrylate copolymer 68103-75-3, Glycidyl methacrylate-phenyl methacrylate copolymer 85920-08-7, Glycidyl methacrylate-methyl isopropenyl ketone copolymer 889447-24-9, Glycidyl methacrylate-phenyl isopropenyl ketone copolymer 889447-26-1, Glycidyl methacrylate-methyl isopropenyl ketone-methyl methacrylate copolymer
RL: DEV (Device component use); TEM (Technical or engineered material use); USES (Uses)
(photosensitive resin composition, ink jet recording head using such composition and method for manufacturing such recording head)

L29 ANSWER 2 OF 11 HCAPLUS COPYRIGHT 2008 ACS on STN
ACCESSION NUMBER: 2003:870564 HCAPLUS Full-text
DOCUMENT NUMBER: 139:371917
TITLE: Direct drawing-type lithographic printing master plates with excellent developing properties and printing resistance
INVENTOR(S): Tashiro, Hiroshi
PATENT ASSIGNEE(S): Fuji Photo Film Co., Ltd., Japan
SOURCE: Jpn. Kokai Tokkyo Koho, 28 pp.
CODEN: JKXXAF
DOCUMENT TYPE: Patent
LANGUAGE: Japanese
FAMILY ACC. NUM. COUNT: 1
PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 2003312159	A	20031106	JP 2002-184872	200206 25

PRIORITY APPLN. INFO.: JP 2002-48053 A

200202
25

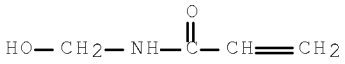
AB The plates, which can be mounted on printers directly after digital scanning exposure, consist of water-resistant supports, hydrophilic layers containing fillers and hydrophilic binder polymers, and image-forming layers containing microencapsulated hydrophobic substances and light-heat converting substances.

IT 29732-09-0, Methyl acrylate-N-methylolacrylamide copolymer
RL: DEV (Device component use); POF (Polymer in formulation); USES (Uses)
(hydrophilic layer; direct drawing-type lithog. master plates containing microencapsulated hydrophobic substances with good developability and printing resistance)

RN 29732-09-0 HCAPLUS
CN 2-Propenoic acid, methyl ester, polymer with N-(hydroxymethyl)-2-propenamide (9CI) (CA INDEX NAME)

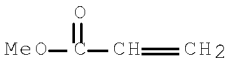
CM 1

CRN 924-42-5
CMF C4 H7 N O2



CM 2

CRN 96-33-3
CMF C4 H6 O2



IC ICM B41N001-14
ICS G03F007-00; G03F007-004; G03F007-11

CC 74-6 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)
Section cross-reference(s): 38

IT 9002-89-5, PVA 117 9003-39-8, Poly(vinyl pyrrolidone) 25322-68-3, Polyethylene glycol 29732-09-0, Methyl acrylate-N-methylolacrylamide copolymer 98566-15-5, Penon HV 2 175069-12-2, PVA 405 273917-62-7, Penon LD 1
RL: DEV (Device component use); POF (Polymer in formulation); USES (Uses)
(hydrophilic layer; direct drawing-type lithog. master plates containing microencapsulated hydrophobic substances with good developability and printing resistance)

L29 ANSWER 3 OF 11 HCAPLUS COPYRIGHT 2008 ACS on STN
ACCESSION NUMBER: 2001:741098 HCAPLUS Full-text
DOCUMENT NUMBER: 135:296220
TITLE: Direct drawing-type lithographic printing master plate

INVENTOR(S): Tashiro, Hiroshi; Kato, Eiichi
PATENT ASSIGNEE(S): Fuji Photo Film Co., Ltd., Japan
SOURCE: Jpn. Kokai Tokkyo Koho, 23 pp.
CODEN: JKXXAF
DOCUMENT TYPE: Patent
LANGUAGE: Japanese
FAMILY ACC. NUM. COUNT: 1
PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 2001277743	A	20011010	JP 2001-15893	200101 24

PRIORITY APPLN. INFO.: JP 2000-14696 A 200001 24

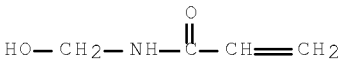
AB The direct drawing-type lithog. printing master plate comprises an image-receiving layer on a water-resistant support, wherein the image-receiving layer contains (1) a sp. metal sulfide grain, (2) a sp. metal hydroxide grain and/or composite oxide grain, (3) a resin in which a metal atom. and O are bonded, and (4) a an organic polymer which forms a hydrogen bond with the resin.

IT 29732-09-0, Methylacrylate-N-methylolacrylamide copolymer
RL: TEM (Technical or engineered material use); USES (Uses)
(direct drawing-type lithog. printing master plate from)

RN 29732-09-0 HCAPLUS
CN 2-Propenoic acid, methyl ester, polymer with N-(hydroxymethyl)-2-propenamide (9CI) (CA INDEX NAME)

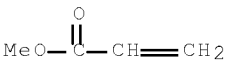
CM 1

CRN 924-42-5
CMF C4 H7 N O2



CM 2

CRN 96-33-3
CMF C4 H6 O2



IC ICM B41N001-14
ICS B41C001-10; B41J002-01

CC 74-6 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)

Section cross-reference(s): 38
IT 1306-23-6, Cadmium monosulfide, uses 1309-33-7, Iron hydroxide (Fe(OH)3) 1309-42-8, Magnesium hydroxide 1314-95-0, Tin monosulfide 1314-98-3, Zinc sulfide, uses 1315-04-4, Antimony pentasulfide 1317-33-5, Molybdenum disulfide, uses 1343-88-0, Magnesium silicate 1344-69-0, Copper hydroxide 9002-89-5, PVA-117 9003-39-8 11119-70-3, Chromium lead oxide 12009-21-1, Barium zirconate 12013-47-7, Calcium zirconate 12018-06-3, Chromium monosulfide 12031-30-0, Lanthanum monosulfide 12035-51-7, Nickel disulfide 12039-13-3, Titanium disulfide 12039-15-5, Zirconium disulfide 12039-19-9, Yttrium sulfide 12054-48-7, Nickel hydroxide 12060-00-3, Lead titanate 12060-01-4, Lead zirconate 12060-59-2, Strontium titanate 12068-85-8, Iron disulfide 12643-13-9, Cobalt silicate 12651-25-1, Zinc titanate 12672-51-4, Cobalt hydroxide 12788-81-7, Aluminum tungsten oxide 13470-04-7, Strontium molybdate 13573-11-0, Magnesium tungstate 13597-65-4, Zinc silicate 17194-00-2, Barium hydroxide 20427-58-1, Zinc hydroxide 21548-73-2, Silver sulfide 21645-51-2, Aluminum hydroxide, uses 25322-68-3, PEG2000 29732-09-0, Methylacrylate-N-methylolacrylamide copolymer 37368-09-5, Zirconium titanate 39377-54-3, Lanthanum hydroxide 51845-71-7, Aluminum molybdate 52110-08-4, Strontium vanadium oxide 52934-19-7, Iridium sulfide 141087-43-6, Methyltrimethoxysilane-tetraethoxysilane copolymer 175069-12-2, PVA405 212716-32-0, Tetramethoxysilane-trimethoxysilane copolymer 273735-04-9, Octyltrimethoxysilane-tetrapropoxysilane copolymer 273735-05-0, 3-Hydroxypropyltrimethoxysilane-tetraethoxysilane copolymer 273735-06-1, 2-Carboxyethyltrimethoxysilane-tetraethoxysilane-copolymer 273735-07-2, 3-Sulfopropyltrimethoxysilane-tetraethoxysilane copolymer 273917-62-7, Penon-ld1 292620-69-0, Tetrabutoxysilane-tetra(2-methoxyethoxy)titanium copolymer 350010-45-6, Germanium hydroxide
RL: TEM (Technical or engineered material use); USES (Uses)
(direct drawing-type lithog. printing master plate from)

L29 ANSWER 4 OF 11 HCAPLUS COPYRIGHT 2008 ACS on STN
ACCESSION NUMBER: 2001:143620 HCAPLUS Full-text
DOCUMENT NUMBER: 134:185992
TITLE: Direct-drawing master plates for offset lithography providing images with good background whiteness
INVENTOR(S): Tashiro, Hiroshi; Kato, Eiichi
PATENT ASSIGNEE(S): Fuji Photo Film Co., Ltd., Japan
SOURCE: Jpn. Kokai Tokkyo Koho, 22 pp.
CODEN: JKXXAF
DOCUMENT TYPE: Patent
LANGUAGE: Japanese
FAMILY ACC. NUM. COUNT: 1
PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 2001054987	A	20010227	JP 2000-170717	20000607
US 6673435	B1	20040106	US 2000-588952	

PRIORITY APPLN. INFO.: JP 1999-159639 A 19990607
JP 1999-159640 A 19990607

AB The master plates, showing good balance of printing durability and hydrophilicity, have ink-receiving layers containing resins with siloxane linkages, polymers which form H bonds with the former, and 0.01-5-μm (average) grains consisting of 5-50% metal (chosen from Zn, Ag, Se, Fe, Pb, Sb, Cd, Cr, Co, Zr, Sn, Ti, Ni, Mg, Mo, La, Pd, Y, In, and/or Ir) sulfides and 50-95% metal (chosen from Mg, Ba, Ge, Sn, Zn, Pb, La, Zr, V, Cr, Mo, W, Mn, Co, Ti, Ni, Fe, and/or Cu) oxides.

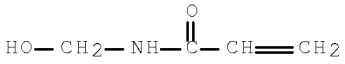
IT 28502-06-9, N-Methylolacrylamide-methyl methacrylate copolymer
RL: TEM (Technical or engineered material use); USES (Uses)
(ink-receiving layers; direct-drawing master plates for offset lithog. providing images with good background whiteness)

RN 28502-06-9 HCAPLUS

CN 2-Propenoic acid, 2-methyl-, methyl ester, polymer with N-(hydroxymethyl)-2-propenamide (CA INDEX NAME)

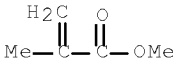
CM 1

CRN 924-42-5
CMF C4 H7 N O2



CM 2

CRN 80-62-6
CMF C5 H8 O2



IC ICM B41N001-14
ICS C08K003-22; C08K003-30; C08L083-04; C08L101-00

CC 74-6 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)
Section cross-reference(s): 38

IT 9002-89-5, PVA 117 9003-39-8, Poly(vinyl pyrrolidone) 11099-06-2, Tetraethoxysilane homopolymer 25322-68-3, Polyethylene glycol 28502-06-9, N-Methylolacrylamide-methyl methacrylate copolymer 43134-20-9, Polyethyleneimine acetate 65697-21-4, Benzyl methacrylate-methacrylic acid copolymer

98566-15-5, Penon HV 2 141087-43-6, Methyltrimethoxysilane-tetraethoxysilane copolymer 175069-12-2, PVA 405 182559-23-5 193617-85-5, Tetramethoxysilane-triethoxysilane copolymer 273735-04-9, Octyltrimethoxysilane-tetrapropoxysilane copolymer 273735-05-0, 3-Hydroxypropyltrimethoxysilane-tetraethoxysilane copolymer 273735-06-1, 2-Carboxyethyltrimethoxysilane-tetraethoxysilane copolymer 273735-07-2, 3-Sulfopropyltrimethoxysilane-tetraethoxysilane copolymer 273917-51-4, Penon F 3 273917-62-7, Penon LD 1 291532-16-6, Methyltrimethoxysilane-tetrapropoxysilane copolymer 326852-59-9 326852-60-2
RL: TEM (Technical or engineered material use); USES (Uses)
(ink-receiving layers; direct-drawing master plates for offset lithog. providing images with good background whiteness)

L29 ANSWER 5 OF 11 HCAPLUS COPYRIGHT 2008 ACS on STN
ACCESSION NUMBER: 2000:802002 HCAPLUS Full-text
DOCUMENT NUMBER: 133:357288
TITLE: Direct imaging-type lithographic original plate
INVENTOR(S): Kato, Eiichi; Tashiro, Hiroshi
PATENT ASSIGNEE(S): Fuji Photo Film Co., Ltd., Japan
SOURCE: Jpn. Kokai Tokkyo Koho, 20 pp.
CODEN: JKXXAF
DOCUMENT TYPE: Patent
LANGUAGE: Japanese
FAMILY ACC. NUM. COUNT: 1
PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 2000313177	A	20001114	JP 2000-55759	200003 01
PRIORITY APPLN. INFO.:			JP 1999-54323	A 199903 02

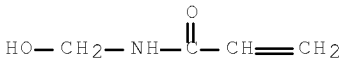
AB The title lithog. original plate possesses, on a water-resistant support, an image-receiving layer containing complex oxides particles with average particle diameter 0.01-10 μm (≥1 metal atom constituting the oxides is selected from Mg, Al, Si, Ti, Zr, Cr, V, Mo, Sn, W, and Nb) and a binder resin containing a composite of a resin having siloxane bonds in which the Si links via O atom and an organic polymer having groups capable of forming H bond with the siloxane bond-containing resin. The original plate is capable of producing a large number of high quality printings with clear images and without greasing.

IT 29732-09-0, Methyl acrylate-N-methylol acrylamide copolymer
RL: DEV (Device component use); USES (Uses)
(electrophotog.-manufactured direct-imaging lithog. plate containing complex metal oxide and siloxane binder)

RN 29732-09-0 HCAPLUS
CN 2-Propenoic acid, methyl ester, polymer with N-(hydroxymethyl)-2-propenamide (9CI) (CA INDEX NAME)

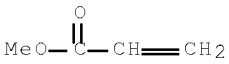
CM 1

CRN 924-42-5
CMF C4 H7 N O2



CM 2

CRN 96-33-3
CMF C4 H6 O2



IC ICM B41N001-14
ICS G03F007-00; G03F007-075
CC 74-6 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)
IT 7758-97-6, Lead chromate 9002-89-5, PVA 117 9003-39-8, Polyvinylpyrrolidone 11099-06-2, Tetraethoxysilane homopolymer 12009-21-1, Barium zirconate 12013-47-7, Calcium zirconate 12035-39-1, Nickel titanate 12036-31-6, Lead stannate 12036-43-0, Zinc titanate (ZnTiO3) 12036-70-3, Zirconium titanate (ZrTiO4) 12047-27-7, Barium titanate, uses 12060-01-4, Lead zirconate 12060-59-2, Strontium titanate 12143-36-1 13455-33-9, Cobalt silicate (Co2SiO4) 13470-04-7, Strontium molybdate 13573-11-0, Magnesium tungstate 13776-74-4, Magnesium silicate (MgSiO3) 13814-85-2, Zinc silicate 15123-80-5, Aluminum molybdate (Al2Mo3O12) 15123-82-7, Aluminum tungsten oxide (Al2W3O12) 18454-12-1, Lead chromate oxide (Pb2(CrO4)O) 25322-68-3 29732-09-0, Methyl acrylate-N-methylol acrylamide copolymer 39318-32-6, Magnesium zirconate 98566-15-5, PENON HV 2 134043-54-2 141087-43-6, Methyltrimethoxysilane-tetraethoxysilane copolymer 167308-66-9, Tetraethoxysilane-triethoxysilane copolymer 175069-12-2, PVA 405 273735-04-9, Octyltrimethoxysilane-tetrapropoxysilane copolymer 273735-05-0, 3-Hydroxypropyltrimethoxysilane-tetraethoxysilane copolymer 273735-06-1, 2-Carboxyethyltrimethoxysilane-tetraethoxysilane copolymer 273735-07-2, 3-Sulfopropyltrimethoxysilane-tetraethoxysilane copolymer 273917-62-7, PENON LD 1 292620-69-0
RL: DEV (Device component use); USES (Uses)
(electrophotog.-manufactured direct-imaging lithog. plate containing complex metal oxide and siloxane binder)

L29 ANSWER 6 OF 11 HCAPLUS COPYRIGHT 2008 ACS on STN
ACCESSION NUMBER: 2000:634883 HCAPLUS Full-text
DOCUMENT NUMBER: 133:230413
TITLE: Direct imaging-type lithographic original plate
INVENTOR(S): Tashiro, Hiroshi; Kato, Eiichi
PATENT ASSIGNEE(S): Fuji Photo Film Co., Ltd., Japan
SOURCE: Jpn. Kokai Tokkyo Koho, 20 pp.
CODEN: JKXXAF
DOCUMENT TYPE: Patent
LANGUAGE: Japanese
FAMILY ACC. NUM. COUNT: 1

PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 2000247052	A	20000912	JP 1999-371049	19991227
PRIORITY APPLN. INFO.:			JP 1998-373685	A 19981228

AB The title lithog. original plate possesses, on a water-resistant support, an image-receiving layer containing metal oxide particles with average particle diameter 0.01-5 μm (the metal constituting the metal oxide is ≥1 selected from Mg, Ba, Ge, Sn, Zn, Pb, La, Zr, V, Cr, Mo, W, Mn, Co, Ni, and Cu) and a binder resin including a composite of a siloxane bond-containing resin in which the Si atoms link through O atom and an organic polymer having groups capable of forming H bond with the resin. The offset printing plate obtained from the original plate produces high quality printings with clear images and without scumming and shows high printing durability.

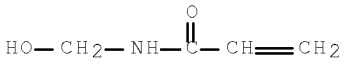
IT 29732-09-0, Methyl acrylate-N-methylolacrylamide copolymer
RL: DEV (Device component use); USES (Uses)
(direct imaging-type lithog. plate containing metal oxide particle and binder having siloxane bond)

RN 29732-09-0 HCAPLUS

CN 2-Propenoic acid, methyl ester, polymer with N-(hydroxymethyl)-2-propenamide (9CI) (CA INDEX NAME)

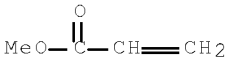
CM 1

CRN 924-42-5
CMF C4 H7 N O2



CM 2

CRN 96-33-3
CMF C4 H6 O2



IC ICM B41N001-14
ICS G03F007-00

CC 74-6 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)
Section cross-reference(s): 38

IT 1304-28-5, Barium oxide, uses 1307-96-6, Cobalt oxide, uses 1308-04-9, Cobalt oxide (Co2O3) 1308-38-9, Chromium oxide, uses

1309-48-4, Magnesium oxide, uses 1309-60-0, Lead oxide
1310-53-8, Germanium oxide, uses 1312-81-8, Lanthanum oxide
1313-13-9, Manganese oxide, uses 1313-27-5, Molybdenum oxide, uses
1313-99-1, Nickel oxide, uses 1314-13-2, Finex 50, uses
1314-23-4, Zirconium oxide, uses 1314-35-8, Tungsten oxide (WO3), uses 1314-41-6, Lead oxide 1317-39-1, Copper oxide, uses
1344-43-0, Manganese oxide, uses 9002-89-5, PVA 117 9003-39-8, Polyvinylpyrrolidone 11099-06-2, Silicic acid ethyl ester
12036-21-4, Vanadium oxide (VO2) 12036-22-5, Tungsten oxide (WO2)
18282-10-5, Tin oxide (SnO2) 25322-68-3, Poly(ethylene glycol)
29732-09-0, Methyl acrylate-N-methylolacrylamide copolymer
98566-15-5, PENON HV 2 134043-54-2 141087-43-6, Methyltrimethoxysilane-tetraethoxysilane copolymer 175069-12-2, PVA 405 193617-85-5, Tetramethoxysilane-triethoxysilane copolymer
273735-04-9, Octyltrimethoxysilane-tetrapropoxysilane copolymer
273735-05-0, 3-Hydroxypropyltrimethoxysilane-tetraethoxysilane copolymer 273735-06-1, 2-Carboxyethyltrimethoxysilane-tetraethoxysilane copolymer 273735-07-2, 3-Sulfopropyltrimethoxysilane-tetraethoxysilane copolymer
273917-62-7, Penon LD 1 291532-16-6, Methyltrimethoxysilane-tetrapropoxysilane copolymer
RL: DEV (Device component use); USES (Uses)
(direct imaging-type lithog. plate containing metal oxide particle and binder having siloxane bond)

L29 ANSWER 7 OF 11 HCAPLUS COPYRIGHT 2008 ACS on STN
ACCESSION NUMBER: 2000:631726 HCAPLUS Full-text
DOCUMENT NUMBER: 133:245112
TITLE: Direct imaging-type lithographic plate containing composite resin binder
INVENTOR(S): Kato, Eiichi; Tashiro, Hiroshi
PATENT ASSIGNEE(S): Fuji Photo Film Co., Ltd., Japan
SOURCE: Jpn. Kokai Tokkyo Koho, 20 pp.
CODEN: JKXXAF
DOCUMENT TYPE: Patent
LANGUAGE: Japanese
FAMILY ACC. NUM. COUNT: 1
PATENT INFORMATION:

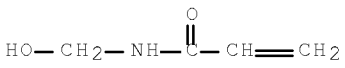
PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 2000247051	A	20000912	JP 1999-371048	19991227
PRIORITY APPLN. INFO.:			JP 1998-373686	A 19981228

OTHER SOURCE(S): MARPAT 133:245112
AB The plate comprises a water resistant support having thereon an image receiving layer containing at least a composite resin binder which comprises (A) a resin bonded with a metal hydroxide particle M(OH)x (M = Mg, Ba, Al, Ti, Zn, Cu, Ni, Sn, Co, Ge, Fe, La; x = valence number of metal M) and Si through O atom and (B) an organic polymer with a group forming a hydrogen bond with the resin. It provides images without background fog and prints without defects and distortion.
IT 29732-09-0, Methyl acrylate-N-methylolacrylamide copolymer
RL: DEV (Device component use); USES (Uses)
(direct imaging-type lithog. plate containing metal

hydroxide particle and binder having siloxane bond)
RN 29732-09-0 HCAPLUS
CN 2-Propenoic acid, methyl ester, polymer with N-(hydroxymethyl)-2-propenamide (9CI) (CA INDEX NAME)

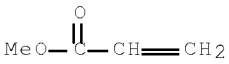
CM 1

CRN 924-42-5
CMF C4 H7 N O2



CM 2

CRN 96-33-3
CMF C4 H6 O2



IC ICM B41N001-14
ICS G03F007-00
CC 74-6 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)
IT 1309-42-8, Magnesium hydroxide 9002-89-5, PVA 117 9003-39-8, Polyvinylpyrrolidone 11099-06-2, Silicic acid ethyl ester 12024-99-6, Germanium hydroxide (Ge(OH)2) 12054-48-7, Nickel hydroxide 12651-23-9, Titanium hydroxide 14507-19-8, Lanthanum hydroxide 17194-00-2, Barium hydroxide 20427-58-1, Zinc hydroxide 20427-59-2, Copper hydroxide 21041-93-0, Cobalt hydroxide (Co(OH)2) 21645-51-2, Aluminum hydroxide, uses 25322-68-3, Poly(ethylene glycol) 29732-09-0, Methyl acrylate-N-methylolacrylamide copolymer 39311-68-7, Tin hydroxide 64255-44-3 98566-15-5, PENON HV 2 141087-43-6, Methyltrimethoxysilane-tetraethoxysilane copolymer 175069-12-2, PVA 405 193617-85-5, Tetramethoxysilane-triethoxysilane copolymer 273735-04-9, Octyltrimethoxysilane-tetrapropoxysilane copolymer 273735-05-0, 3-Hydroxypropyltrimethoxysilane-tetraethoxysilane copolymer 273735-06-1, 2-Carboxyethyltrimethoxysilane-tetraethoxysilane copolymer 273735-07-2, 3-Sulfopropyltrimethoxysilane-tetraethoxysilane copolymer 273917-62-7, Penon LD 1 292620-69-0
RL: DEV (Device component use); USES (Uses)
(direct imaging-type lithog. plate containing metal hydroxide particle and binder having siloxane bond)

L29 ANSWER 8 OF 11 HCAPLUS COPYRIGHT 2008 ACS on STN
ACCESSION NUMBER: 2000:570345 HCAPLUS Full-text
DOCUMENT NUMBER: 133:142630
TITLE: Lithographic printing plate precursor
INVENTOR(S): Tashiro, Hiroshi; Kato, Eiichi
PATENT ASSIGNEE(S): Fuji Photo Film Co., Ltd., Japan

SOURCE: Brit. UK Pat. Appl., 89 pp.
CODEN: BAXXDU
DOCUMENT TYPE: Patent
LANGUAGE: English
FAMILY ACC. NUM. COUNT: 1
PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
GB 2344062	A	20000531	GB 1999-26554	19991109
GB 2344062	B	20010131		
US 6472055	B1	20021029	US 1999-436807	19991109

PRIORITY APPLN. INFO.: JP 1998-319176 A 19981110
JP 1999-25263 A 19990202

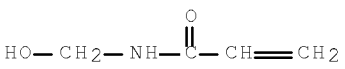
AB The invention relates to a direct drawing type lithog. printing plate precursor and, particularly, to a direct drawing type lithog. printing plate precursor capable of providing a printing plate which enables to print a great number of printed matter having clear images free from background strain. A direct drawing type lithog. printing plate precursor comprising a water-resistant support has thereon an image receiving layer containing: at least one metal oxide hydrate having an average particle size of from 0.01 to 5μm and comprising a metal atom selected from Mg, Al, Zn, Ge, Ti, Co, Zr, Sn, Fe, Cu, Ni, Pb, Pd, Cd, Mo, Cr, Ga, Mn, V, Ce, and La: and a binder resin containing a complex comprising: a resin containing a siloxane bond in which a silicon atom is connected with an oxygen atom; and an organic polymer containing a group capable of forming a hydrogen bond with the resin containing a siloxane bond,\.

IT 29732-09-0
RL: NUU (Other use, unclassified); USES (Uses)
(preparation of direct drawing type lithog. printing plate precursor using)

RN 29732-09-0 HCAPLUS
CN 2-Propenoic acid, methyl ester, polymer with N-(hydroxymethyl)-2-propenamide (9CI) (CA INDEX NAME)

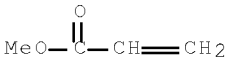
CM 1

CRN 924-42-5
CMF C4 H7 N O2



CM 2

CRN 96-33-3
CMF C4 H6 O2



IC ICM B41N001-14
ICS B41N001-10; G03G013-28
CC 74-6 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)
IT 78-10-4, Tetraethoxysilane 682-01-9, Tetrapropoxysilane 998-30-1, Triethoxysilane 1185-55-3, Methyltrimethoxysilane 1306-19-0, Cadmium oxide, uses 1310-53-8, Germanium oxide, uses 1312-81-8, Lanthanum oxide 1313-99-1, Nickel oxide, uses 1314-08-5, Palladium oxide 1314-13-2, Zinc oxide (ZnO), uses 1314-23-4, Zirconium oxide, uses 1332-29-2, Tin oxide 1332-37-2, Iron oxide, uses 1335-25-7, Lead oxide 1344-70-3, Copper oxide 2031-67-6, Methyltriethoxysilane 3069-40-7, Octyltrimethoxysilane 4766-57-8, Tetrabutoxysilane 9003-39-8, Poly(vinylpyrrolidone) 11098-99-0, Molybdenum oxide 11099-11-9, Vanadium oxide 11104-61-3, Cobalt oxide 11114-17-3, FC 430 11118-57-3, Chromium oxide 11129-18-3, Cerium oxide 12024-21-4, Gallium oxide 17872-99-0, Benzyltrimethoxysilane 29732-09-0 51833-27-3 53764-54-8, 3-Hydroxypropyltrimethoxysilane 79059-66-8, 3-Sulfopropyltrimethoxysilane 93629-90-4 98566-15-5, PENON ZP-2 132989-33-4 134043-54-2 139357-99-6 273917-51-4, PENON F3 273917-62-7, PENON LD-1
RL: NUU (Other use, unclassified); USES (Uses)
(preparation of direct drawing type lithog. printing plate precursor using)

L29 ANSWER 9 OF 11 HCAPLUS COPYRIGHT 2008 ACS on STN
ACCESSION NUMBER: 1995:794929 HCAPLUS Full-text
DOCUMENT NUMBER: 123:183494
ORIGINAL REFERENCE NO.: 123:32381a,32384a
TITLE: Color filter, method for manufacturing it, and liquid crystal panel.
INVENTOR(S): Shiba, Shoji; Sato, Hiroshi; Shirota, Katsuhiro; Yokoi, Hideto; Kashiwazaki, Akio; Murai, Keiichi; Miyazaki, Takeshi
PATENT ASSIGNEE(S): Canon K. K., Japan
SOURCE: Eur. Pat. Appl., 49 pp.
CODEN: EPXXDW
DOCUMENT TYPE: Patent
LANGUAGE: English
FAMILY ACC. NUM. COUNT: 1
PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
EP 655647	A1	19950531	EP 1994-118432	19941123
EP 655647	B1	20020227		

R: AT, BE, CH, DE, DK, ES, FR, GB, GR, IE, IT, LI, LU, NL, PT, SE

JP 08075916	A	19960322	JP 1994-286616	199411 21
JP 2872594	B2	19990317		
TW 417034	B	20010101	TW 1994-83110881	199411 22
EP 942326	A1	19990915	EP 1999-110503	199411 23
EP 942326	B1	20030611		
R: AT, BE, CH, DE, DK, ES, FR, GB, GR, IT, LI, LU, NL, SE, PT, IE				
EP 942327	A1	19990915	EP 1999-110504	199411 23
EP 942327	B1	20081029		
R: AT, BE, CH, DE, DK, ES, FR, GB, GR, IT, LI, LU, NL, SE, PT, IE				
AT 213845	T	20020315	AT 1994-118432	199411 23
AT 242889	T	20030615	AT 1999-110503	199411 23
JP 08075917	A	19960322	JP 1994-289851	199411 24
JP 2872595	B2	19990317		
CN 1122007	A	19960508	CN 1994-114096	199411 24
CN 1082672	C	20020410		
KR 173149	B1	19990320	KR 1994-31035	199411 24
JP 08136726	A	19960531	JP 1994-299633	199412 02
JP 2872596	B2	19990317		
US 5716740	A	19980210	US 1996-695667	199608 08
US 6180294	B1	20010130	US 1997-965466	199711 06
US 6686104	B1	20040203	US 2000-679342	200010 04
PRIORITY APPLN. INFO.:			JP 1993-293395 A	199311 24
			JP 1993-322133 A	199312 21
			JP 1994-150870 A	199407 01

JP 1994-150874	A	199407 01
JP 1994-220049	A	199409 14
US 1994-345710	B1	199411 22
EP 1994-118432	A3	199411 23
US 1996-695667	A3	199608 08
US 1997-965466	A3	199711 06

AB Provided is a color filter which comprises a substrate and a resin layer on the substrate, the resin layer containing a plurality of colored portions of different colors and noncolored portions. The colored portions are made by ink-printing, nonimpact, ink-jet printing.

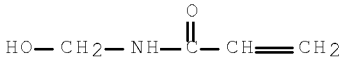
IT 28502-06-9, Methyl methacrylate-N-methylolacrylamide copolymer
RL: MOA (Modifier or additive use); POF (Polymer in formulation); USES (Uses)
(ink jet printing on photosensitive composition for color filter for liquid-crystal display panels)

RN 28502-06-9 HCAPLUS

CN 2-Propenoic acid, 2-methyl-, methyl ester, polymer with N-(hydroxymethyl)-2-propenamide (CA INDEX NAME)

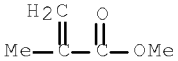
CM 1

CRN 924-42-5
CMF C4 H7 N O2



CM 2

CRN 80-62-6
CMF C5 H8 O2



IC ICM G03C007-12
ICS G02F001-1335; B41M005-00
CC 74-4 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)
IT 140-95-4, Dimethylolurea 9003-08-1, Sumitex M3 9004-62-0, Ah-15 9004-64-2, Hpc-h 9012-09-3, Cellulose triacetate 26355-01-1, Hydroxyethyl methacrylate-methyl methacrylate copolymer 28502-06-9, Methyl methacrylate-N-methylolacrylamide copolymer 38193-53-2 125026-29-1 129401-30-5 160109-42-2 167860-29-9 167860-30-2 167860-31-3
RL: MOA (Modifier or additive use); POF (Polymer in formulation); USES (Uses)
(ink jet printing on photosensitive composition for color filter for liquid-crystal display panels)

L29 ANSWER 10 OF 11 HCAPLUS COPYRIGHT 2008 ACS on STN
ACCESSION NUMBER: 1987:468249 HCAPLUS Full-text
DOCUMENT NUMBER: 107:68249
ORIGINAL REFERENCE NO.: 107:11125a,11128a
TITLE: Optical recording card
INVENTOR(S): Sakai, Nobuhiko
PATENT ASSIGNEE(S): Dai Nippon Printing Co., Ltd., Japan
SOURCE: Jpn. Kokai Tokkyo Koho, 12 pp.
CODEN: JKXXAF
DOCUMENT TYPE: Patent
LANGUAGE: Japanese
FAMILY ACC. NUM. COUNT: 1
PATENT INFORMATION:

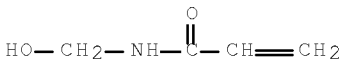
PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 61214151	A	19860924	JP 1985-55160	19850319

PRIORITY APPLN. INFO.: JP 1985-55160 19850319

AB In an optical card for recording and reproducing information, 2 types of regions are available; regions for recording codified information and regions for recording visible information.
IT 28502-06-9
RL: USES (Uses)
(photosensitive layer for optical recording card containing)
RN 28502-06-9 HCAPLUS
CN 2-Propenoic acid, 2-methyl-, methyl ester, polymer with N-(hydroxymethyl)-2-propenamide (CA INDEX NAME)

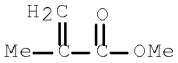
CM 1

CRN 924-42-5
CMF C4 H7 N O2



CM 2

CRN 80-62-6
CMF C5 H8 O2



IC ICM G11B007-24
ICS B42D015-02; G03C001-72; G06K019-06
CC 74-12 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)
IT 7647-10-1, Palladium chloride 9003-20-7 28502-06-9
50543-78-7 52229-50-2
RL: USES (Uses)
(photosensitive layer for optical recording card containing)

L29 ANSWER 11 OF 11 HCAPLUS COPYRIGHT 2008 ACS on STN
ACCESSION NUMBER: 1976:82569 HCAPLUS Full-text
DOCUMENT NUMBER: 84:82569
ORIGINAL REFERENCE NO.: 84:13463a,13466a
TITLE: Photosensitive material for lithographic plate
PATENT ASSIGNEE(S): Eastman Kodak Co., USA
SOURCE: Neth. Appl., 41 pp.
CODEN: NAXXAN
DOCUMENT TYPE: Patent
LANGUAGE: Dutch
FAMILY ACC. NUM. COUNT: 2
PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
NL 7414518	A	19750512	NL 1974-14518	19741107
CA 1041698	A1	19781031	CA 1974-212535	19741029
FR 2251031	A1	19750606	FR 1974-36756	19741106
IT 1025479	B	19780810	IT 1974-29174	19741106
BE 821970	A1	19750507	BE 1974-150315	19741107
DE 2452761	A1	19750515	DE 1974-2452761	197411

				07
JP 50078402	A	19750626	JP 1974-128850	
				197411
				08
AU 7475175	A	19760513	AU 1974-75175	
				197411
				08
PRIORITY APPLN. INFO.:			GB 1973-51941	A
				197311
				08

AB For relief images for lithog. plates or photoresists, film-forming polymers are used which contain ethylene and halogenated Me groups, such as trichloroacetyl or tribromoacetyl, and are soluble in aqueous and organic solvents. They are insolubilized by an uv exposure in the presence of 1-10% of a metal carbonyl compound For their preparation mixture of a C1-4 alkyl methacrylate and a hydroxyalkyl methacrylate in the ratio 5:1 is polymerized and condensed with an acid or acid chloride. Part of the methacrylate may be replaced with acrylamide or acrylic acid for increased solubility in aqueous solvents. Thus, a Me methacrylate-2-hydroxyethyl methacrylate prepolymer was reacted in 1,2-dichloroethane with Cl3CCOCl and then with acryloyl chloride. The condensate solution (10% solids) 3 ml was mixed with a 4% cyclohexanone solution of Mn2(CO)10 0.5 ml, coated as a 2-μ (dry) layer on an anodized Al plate precoated with polyacrylamide, exposed to a high-pressure 125-W lamp at 46 cm for 5 min, developed in a mixture of EtOH 100, H2O 20, and Teepol 0.5 ml, and treated with a desensitizing gum solution to give a lithog. plate.

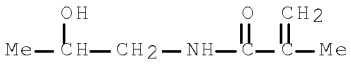
IT 31292-69-0D, 2-Propenamide, N-(2-hydroxypropyl)-2-methyl-, polymer with methyl 2-methyl-2-propenoate, reaction products with acid chlorides
RL: USES (Uses)
(photopolymerable compns. containing, for lithographic plates and photoresists)

RN 31292-69-0 HCAPLUS

CN 2-Propenoic acid, 2-methyl-, methyl ester, polymer with N-(2-hydroxypropyl)-2-methyl-2-propenamide (CA INDEX NAME)

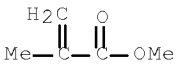
CM 1

CRN 21442-01-3
CMF C7 H13 N O2



CM 2

CRN 80-62-6
CMF C5 H8 O2



IC G03C
CC 74-5 (Radiation Chemistry, Photochemistry, and Photographic Processes)
IT 76-02-8D, Acetyl chloride, trichloro-, reaction products with methacrylate copolymers 814-68-6D, 2-Propenoyl chloride, reaction products with methacrylate copolymers 920-46-7D, 2-Propenoyl chloride, 2-methyl-, reaction products with methacrylate copolymers 10588-31-5D, Acetyl bromide, tribromo-, reaction products with methacrylate copolymers 31292-69-0D, 2-Propenamide, N-(2-hydroxypropyl)-2-methyl-, polymer with methyl 2-methyl-2-propenoate, reaction products with acid chlorides 58308-21-7D, Glycine, N-(1-oxo-2-propenyl)-, ethyl ester, polymer with 2-hydroxyethyl 2-methyl-2-propenoate and methyl 2-methyl-2-propenoate, reaction products with acid chlorides 58308-23-9D, 2-Propenamide, N-(1-methylethyl)-, polymer with 2-hydroxyethyl 2-methyl-2-propenoate and methyl 2-methyl-2-propenoate, reaction products with acid chlorides 58308-24-0D, 2-Propenamide, 2-methyl-, polymer with 2-hydroxyethyl 2-methyl-2-propenoate and methyl 2-methyl-2-propenoate, reaction products with acid chlorides 58308-25-1D, 2-Propenamide, N-(2-hydroxypropyl)-2-methyl-, polymer with butyl 2-methyl-2-propenoate and methyl 2-methyl-2-propenoate, reaction products with acid chlorides 58308-27-3D, 2-Propenamide, N-(2-hydroxypropyl)-2-methyl-, polymer with methyl 2-methyl-2-propenoate and 2-propenenitrile, reaction products with acid chlorides
RL: USES (Uses)
(photopolymerable compns. containing, for lithographic plates and photoresists)

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